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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR			
09/539,458	03/30/2000	Mark S. Chang	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
			1346P/DA01028	8108	
Kelly K. Kordzik, Winstead Sechrest & Minick P.C. 5400 Renaissance Tower			EXAMINER		
			PHAM, HOAI V		
1201 Elm Stree Dallas, TX 75	-		ART UNIT PAPER NUMBER		
Danas, IA /.	270		2814		
			DATE MAILED: 11/10/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	<del>000</del>			
Office Action Summary		09/539,458	CHANG ET AL.				
		Examiner	Art Unit				
		Hoai v Pham	2814				
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover she	et with the correspondence address	·			
A SHOTHE II - Exter after - If the - If NO - Failur - Any re	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. In period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, apply received by the Office later than three months after the mailing displayed patent term adjustment. See 37 CFR 1.704(b).	IS SET TO EXPIRE  36(a). In no event, however, r  within the statutory minimum will apply and will expire SIX (6)	E 3 MONTH(S) FROM  may a reply be timely filed  of thirty (30) days will be considered timely.  i) MONTHS from the mailing date of this communication.				
1)🖂	)⊠ Responsive to communication(s) filed on <u>08 October 2004</u> .						
2a)⊠	TI:	s action is non-final.					
3) Disposition	Since this application is in condition for alloward closed in accordance with the practice under Expn of Claims	nce except for forma	matters, prosecution as to the mer 5 C.D. 11, 453 O.G. 213.	its is			
4)🖂	Claim(s) <u>1-3 and 8-21</u> is/are pending in the app	olication.					
	4a) Of the above claim(s) <u>8-16</u> is/are withdrawn from consideration.						
6)⊠ (	6)⊠ Claim(s) <u>1-3 and 17-20</u> is/are rejected.						
7)🛛 (	Claim(s) <u>21</u> is/are objected to.						
8) (Application	Claim(s) are subject to restriction and/or on Papers	election requirement					
9) <u></u> ⊤	he specification is objected to by the Examiner.						
	ne drawing(s) filed on <u>30 March 2000</u> is/are: a)[		elected to by the Evaminar				
	Applicant may not request that any objection to the	drawing(s) be held in a	bevance See 37 CFR 1.85(a)				
11) 🗌 Th	11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.						
	If approved, corrected drawings are required in reply	to this Office action.					
12) 🗌 Th	12) The oath or declaration is objected to by the Examiner.						
Priority un	der 35 U.S.C. §§ 119 and 120						
13) 🗌 🛭 A	cknowledgment is made of a claim for foreign p	priority under 35 U.S.	C. § 119(a)-(d) or (f)				
a) <u></u>	All b) Some * c) None of:	,	0. 3				
1	1. Certified copies of the priority documents have been received.						
2	2. Certified copies of the priority documents have been received in Application No						
	Copies of the certified copies of the priority application from the International Bures the attached detailed Office action for a list of	documents have be	en received in this National Stage				
14) <u></u> Ac∤	knowledgment is made of a claim for domestic p	priority under 35 U.S.	C. § 119(e) (to a provisional applier	ation)			
a) L	The translation of the foreign language provise the translation of the foreign language provise for the translation of the foreign language provise for the translation of the foreign language provise translation is the foreign language provise translation of the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provise translation in the foreign language provise translation is the foreign language provi	sional application has	s heen recoived	ation).			
Attachment(s)	)		0. 99 120 and/or 121,				
2) 🔲 Notice o	f References Cited (PTO-892)  f Draftsperson's Patent Drawing Review (PTO-948)  ion Disclosure Statement(s) (PTO-1449) Paper No(s)		ew Summary (PTO-413) Paper No(s) of Informal Patent Application (PTO-152)	<b>.</b> ·			

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#### **DETAILED ACTION**

## Response to Amendment

1. Applicant's request for reconsideration of the finality of the rejection of the last Office action is persuasive and, therefore, the finality of that action is withdrawn.

# Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1, 17, and 18 are rejected under 35 U.S.C. 102(e) as being anticipated by Lee et al. [U.S. Pat. 6,197,639] newly cited.

With respect to claim 1, Lee et al. (fig. 12, cols. 2-5) discloses a flash memory device comprising:

a plurality of gate stacks including a plurality of floating gates (57a) and a plurality of control gates (63a) disposed on a semiconductor substrate (51);

at least one component (57, 63) including a polysilicon layer having a top surface, wherein the at least one component (57, 63) is formed on a field oxide region (53) configured to separate the plurality of gate stacks;

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a silicide (65a) on the top surface of the polysilicon layer of the at least one component (57, 63).

an insulating layer (81) covering the plurality of gate stacks, the at least one component and the silicide, the insulating layer having a plurality of contact holes (85, 87, 91) therein.

With respect to claim 17, Lee et al. (fig. 12, cols. 2-5) discloses a flash memory device comprising:

a gate insulating layer (55);

a gate stack formed on the insulating layer, wherein the gate stack comprises:

a first floating gate (57a);

an insulating layer formed on the first floating gate (58a); and

a second polysilicon layer (63a) formed on the insulating layer.

a field oxide region (53) located adjacent to the gate insulating layer;

a component (57, 63) located on the field oxide region (53), wherein the component (57, 63) is formed from one of the first and the second polysilicon layer; and a silicide layer (65a) formed on the component.

With respect to claim 18, Lee et al. discloses that the silicide layer (65a) prevents etching through the polysilicon layer (63) (see fig. 10).

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## Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 6. Claims 2, 3, 19 and 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lee et al. [U.S. Pat. 6,197,639] newly cited, in view of Ma et al. [U.S. Pat. 5,939,753] previously applied.

Lee et al. discloses all the limitation as claimed above except: the silicide includes a titanium silicide or a cobalt silicide. However, Ma et al. discloses that the silicide layer (108, 109) formed on the polysilicon (58) can be formed of tungsten silicide, molybdenum silicide, titanium silicide or cobalt silicide (see col. 7, lines 48-49 and col. 8, lines 1-7). Therefore, it would have been obvious to one of ordinary skill in the art at to select either titanium silicide or cobalt silicide on the component in the

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device of Lee et al. because as taught by Ma et al., such materials are equivalence for their use in the semiconductor art as to form a dual-layer structure with low resistance, which is made up of a polysilicon and metal silicide.

## Allowable Subject Matter

7. Claim 21 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

#### Response to Arguments

8. Applicant's arguments with respect to claims 1-3 and 17-20 have been considered but are most in view of the new ground(s) of rejection.

#### Conclusion

- 9. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).
- 10. A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the

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shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

- 11. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hoai v Pham whose telephone number is 571-272-1715. The examiner can normally be reached on M-F.
- 12. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael M Fahmy can be reached on 571-272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.
- 13. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

HOAI PHAM PRIMARY EXAMINER

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